### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

Milan R. Kokta, et al.

Title:

MATERIALS FOR USE IN OPTICAL AND OPTOELECTRONIC

**APPLICATIONS** 

Application No.: NEW APPLICATION

Filed:

**HEREWITH** 

Atty. Docket No.: 1035-BI3918-CIP

MS PATENT APPLICATION **COMMISSIONER FOR PATENTS** PO Box 1450 Alexandria, VA 22313-1450

# INFORMATION DISCLOSURE STATEMENT TRANSMITTAL

Dear Sir:

Pursuant to 37 C.F.R. § 1.56, § 1.97 and § 1.98, the undersigned brings the patents, publications, applications or other information identified in the attached:

$\boxtimes$	Form(s) PTO/SB/08A and/or PTO	)/SB/08B
	Other: <u>n/a</u>	

to the Examiner's attention in the above-identified application. These references were cited in . Accordingly, in accordance with C.F.R. §1.98(d), , filed parent Application No. copies of the references are not being supplied herewith. Citation of such information shall not be construed as:

- an admission that the information necessarily is, or corresponds to, prior art with 1. respect to the instant invention;
- a representation that a search has been made, other than as described below; or 2.
- an admission that the information cited herein is, or is considered to be, material 3. to patentability as defined in § 1.56(b).

For each item of information listed that is not in the English language, the undersigned has provided a concise explanation of the relevance, such as through (i) an English language abstract, (ii) an English language equivalent application, (iii) reference to discussion in the application, or (iv) if cited in a search report or other action by a foreign patent office in a counterpart foreign application, an English language version of the search report or action that indicates the degree of relevance found by the foreign office.

> EXPRESS MAIL MAILING LABEL NUMBER: EV 335895550 US

# STATEMENT UNDER 37 C.F.R. § 1.704(d)

If the ab May 29, 2000:	ove-identified application is an original application filed on or after
:	each item of information contained in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart application and this communication was not received by any individual designated in § 1.56(c) more than thirty days prior to the filing of this Information Disclosure Statement.
	FEES DUE
This Inf	formation Disclosure Statement is being filed:
	within three months of the filing date of a national application or within three months of entry of the national stage as set forth in § 1.491 in an international application. Therefore, no fee is required.
	before the mailing date of a first Office action on the merits or before the mailing date of a first Office action after the filing of a request for continued examination under § 1.114. Therefore, no fee is believed required.
. 🗆	after the period specified in § 1.97(c), but on or before payment of the issue fee. Accordingly, the fee set forth in § 1.17(p) is required and provided as shown on the attached Fee Transmittal.
filed after the	ever, this Information Disclosure Statement is determined by the USPTO to be period specified in § 1.97(b), the undersigned hereby authorizes the Commissioner see set forth in § 1.17(p) as shown on the attached Fee Transmittal.
Date /	Jeffrey S. Abel, Reg. No. 36,079 Attorney for Applicant(s) TOLER, LARSON & ABEL, L.L.P. P.O. Box 29567 Austin, Texas 78755-9567 (512) 327-5515 (phone) (512) 327-5452 (fax)

# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Substitute for form 1449/PTO

Complete if Known Application Number NEW APPLICATION Filing Date HEREWITH First Named Inventor Milan R. Kokta Attorney Docket Number 1035-BI3918-CIP

Sheet 1 of 3 (use as many sheets as necessary)

U.S. PATENT DOCUMENTS

Examiner Initials *	Cite No.1	U.S. Patent Docume Number Kind Cod (if known	e 2	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	AA	3,655,439		SEITER	04/11/1972	
	AB	3,658,586		WANG	04/25/1972	
	AC	3,796,597		V.R. PORTER, et al.	03/12/1974	
	AD	4,177,321		NISHIZAWA	12/04/1979	
	AE	5,741,724		RAMDANI, et al.	04/21/1998	
·	AF	5.850,410		KURAMATA	12/15/1998	
	AG	5,530,267		BRANDLE, JR., et al.	06/25/1996	<u> </u>
	AH	6,104,529		BRANDLE, JR., et al.	08/15/2000	
	AI	3,883,313		CULLEN, et al.	05/13/1975	
	AJ	5,802,083		BIRNBAUM	09/01/1998	
	AK	2003/0007520	A1	KOKTA, et al.	01/09/2003	

FOREIGN PATENT DOCUMENTS

Examiner Initials *	Cite No.1	Office 3	oreign Patent D Number		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Тв
	AL	EP	0 148 656	A1	AUZEL, et al.	11/16/1984		무
	AM						i	يار

**PUBLICATIONS** 

Examiner Initials *	Cite No.1	Title of Publication			Date of Publication of Cited Document MM-DD-YYYY
	AV	YUMASHEV K.V.,et al., "Co <sup>2+</sup> -doped spinels saturable 1.3-1.6 μm solid state lasers", OSA TRENDS IN OPTC ADVANCED SOLID STATE LASERS., Vol. 34, pp. 236 XP008017966	S AND PHOT	vitches for ONICS.	
	AW	YUMASHEV, K.V., et al., "Passive Q-switching of 1.34- using Co²*:LiGa₅O <sub>8</sub> and Co²*:MgAl₂O₄", CONFERENCE page. XP002242959	E DIGES 1, 200	JU, 1	
	AX	OKTYABRSKY, S., et al., "Crystal structure and defect GaN", MRS Internet J. Nitride Semicond. Res, G6.43, p	pp. 1-6, 1999. _		
	AY	KLEBER, W., et al., "Zur epitaxie von galliumnitrid auf spinell im system GaCl/NH <sub>3</sub> /He", CRYSTAL RESEARC Vol. 10, No. 7, pp. 747-758, 1975. (English Abstract)	CH AND TECH	INOLOGI,	
	AZ	SEIFERT, A., "Nachweis von stapelfehlern in GaN-epit elektronenbeugung", CRYSTAL RESEARCH AND TEC No. 7, pp. 741-746, 1975. (English Abstract)	taxieschichten CHNOLOGY, \	mittels Vol. 10,	
Examine Signatur			Date Considered	Draw line thro	ough citation if not in

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Unique citation designation number. 2 See attached Kinds of U.S. Patent Documents. 3 Enter Office that issued the document, by the twoletter code (WIPO Standard ST.3). 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 5 Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. 6 Applicant is to place a check mark here if English language Translation is attached.

## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Substitute for form 1449/PTO

Examiner

Initials \*

Cite

No 1

BL BM Office 3 Number

Complete if Known

Application Numb r NEW APPLICATION Filing Date HEREWITH First Nam d Inventor Milan R. Kokta Attorney Docket Number 1035-BI3918-CIP

Sheet 2 of 3 (use as many sheets as necessary)

U.S. PATENT DOCUMENTS

Examiner Initials *	Cite No.1	U.S. Patent Docume Number Kind Code (if known)	2	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	BA	6,533,874	B1	VAUDO, et al.	03/18/2003	
	<del></del>	4,627,064		AUZEL, et al.	12/02/1986	
	BB			FALCKENBERG	01/04/1977	
	BC	4,000,977		TAEGRETISE		
	BD				<del> </del>	
	BE				<del></del>	
	BF				<del></del>	<del> </del>
	BG				<del></del>	
	BH					
· -	BI					+
	BJ					
	BK			<u> </u>		<u> </u>
				FOREIGN PATENT DO	CUMENTS	Pages Ta

Pages, Date of Name of Patentee or Columns, Lines, Where Relevant Foreign Patent Document Publication of Applicant Kind Code 2 Cited Document of Cited Document Passages or (if known) MM-DD-YYYY Relevant Figures Appear

#### **PUBLICATIONS** Date of Publication Title of Publication Examiner Cite of Cited Document MM-DD-YYYY No.1 Initials OHSATO, H., et al., "Epitaxial orientation and a growth model of (0 0 • 1) GaN thin film on (1 1 1) spinel substrate, JOURNAL OF CRYSTAL GROWTH, Vol. BW 189/190, pp. 202-207, 1998. YANG, H. –F., et al., "Microstructure evolution of GaN buffer layer on MgAl₂O₄ substrate", JOURNAL OF CRYSTAL GROWTH, Vol. 193, pp. 478-483, 1998. BX DUAN, S., et al., "MOVPE growth of GaN and LEDon (1 1 1) MgAl<sub>2</sub>O<sub>4</sub>", BY JOURNAL OF CRYSTAL GROWTH, Vol. 189/190, pp. 197-201, 1998. SHELDON, R., et al., "Cation Disorder and Vacancy Distribution in ΒZ Nonstoichiometric Magnesium Aluminate Spinel, MgO • Al<sub>2</sub>O<sub>3</sub> ", J. AM. CERAM. SOC., Vol. 82, No. 12, pp. 3293-3298, 1999. Date Examiner Considered Signature

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Unique citation designation number. 2 See attached Kinds of U.S. Patent Documents. 3 Enter Office that issued the document, by the twoletter code (WIPO Standard ST.3). 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. s Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. 6 Applicant is to place a check mark here if English language Translation is attached.

## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Substitute for form 1449/PTO

Complete if Known

Application Number NEW APPLICATION Filing Dat HEREWITH First Named Inv ntor Milan R. K kta Attorney Docket Number 1035-BI3918-CIP

xaminer	Cite	as necessary) PUBLICATIO Title of Publication		[	Date of Publication of Cited Document
nitials *	No.1				MM-DD-YYYY
	AAA	KULESHOV, N.V., et al. "Co-doped spinels: promising state lasers", LONGER WAVELENGTH LASERS AND 2138, pp. 175-182, 1994. XP008017848	THE LIGHT CONTRACT		
	AAB	KULESHOV, N.V., et al., "Absorption and luminescend ion in MgAl <sub>2</sub> O <sub>4</sub> , Vol. 55, no. 5-6, pp. 265-269, 1993. X			
	AAC	NIKISHIN, S.A., et al., "Gas source molecular beam of hydrazine on spinel substrates", APPLIED PHYSICS (19, pp. 2361-2363, 1998. XP000755963	LETTERS, Vol.		
	AAD	HAISMA, et al., "Lattice constant adaptable crystallogic CRYSTAL GROWTH", Vol. 102, pp. 979-993, 1990.	<b> •••</b>		
	AAE	TAMURA, K., et al., "Epitaxial growth of ZnO film on I ScAlMgO <sub>4</sub> (0001) substrates", JOURNAL OF CRYST 214-215, pp. 59-62, 2000. XP004200964	attice-matched AL GROWTH, \	Vol.	
	AAF	WYON, et al., "Czochralshi growth and optical proper aluminum spinel doped with nickel", JOURNAL OF C Vol. 79, pp. 710-713, 1986. XP002250057	KIOIAL OIG		
	AAG	TSUCHIYA, T., et al. "Epitaxial growth of InN films of substrates", JOURNAL OF CRYSTAL GROWTH, Vo. 2000.	on MgAl₂O₄ (1 1 Ы. 220, pp. 185-	1) 190,	
	AAH	KURAMATA, Akito, et al., "High-quality GaN epitaxia metalorganic vapor phase epitazy on (111) MgAl₂O₄ PHYS. LETT., Vol. 67, No. 17, pp. 2521-2523, 1995			
	AAI	MITCHELL, T., "Dislocations and Mechanical Prope spinel single crystals", J. AM. CERAM. SOC., Vol. 8 3316, 1999.	2, 140. 12, pp. 5	gAl₂O₃ 305-	
	AAJ	HELLMAN, E., "Exotic and Mundane substrates for heteroepitaxy", BELL LABORATORIES, THC2, Mur	idy i iii., i ioi	De" THE	
	AAK	KRUGER, M.B., et al., "Equation of state of MgAl <sub>2</sub> O AMERICAN PHYSICAL SOCIETY, Vol. 56, No. 1, p. 10.	<b>p.</b> 1 1, 10011	_	
	AAL	KURAMATA, A., et al., "Properties of GaN epitaxial MgAl <sub>2</sub> O₄ substrate", SOLID-STATE ELECTRONICS 254, 1997.			
	AAM	GRITSYNA, V., et al., "Structure and Electronic state different compositions MgO • n MgAl <sub>2</sub> O <sub>3</sub> :Me", J. Al No. 1, pp. 3365-3373, 1999.	ites of defects in	n spinel of C. Vol. 82.	
			Date	_	
	iner	i de la companya de			

Signature Considered

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered behave considered to the formulation of the considered line in the conformance and not considered line in the considered line in the conformance and not considered line in the considered line in the conformance and not considered line in the considered line in the conformance and not considered line in the Signature conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Unique citation designation number. 2 See attached Kinds of U.S. Patent Documents. 3 Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 5 Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. 6 Applicant is to place a check mark here if English language Translation is attached.